

Serial No.

RD-25,993-7

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Barry Lee-Mean Yang et al. : Group Art Unit:

Serial No. : Examiner:

Filed: : Paper No.: 1

For: **MULTILAYER ARTICLE AND METHOD OF MAKING BY ARC
PLASMA DEPOSITION**

PRELIMINARY AMENDMENT

Assistant Director of Patents and Trademarks
United States Patent and Trademark Office
Washington, DC 20231

Sir:

Please amend the Divisional Application, submitted herewith, of Application
Serial No. 09/271,654, filed March 17, 1999, as follows.

If any additional fees for the accompanying response are required, Applicants
request that this be considered a petition therefor. The Director is hereby authorized to
charge any fees that may be required to Deposit Account 07-0868.

In the Specification:

On page 1, line 2, please insert the following:

--This is a division of Application Serial No. 09/271,654, filed March 17, 1999.--

In the Claims:

Please cancel Claims 1-3, 9-11, 13-16, 20-51 and 59-61, without prejudice.

Marked-up versions of amended Claims 4-7 and 57 are provided in Attachment A, submitted herewith.

Please substitute the following for pending Claim 4:

4. (Amended) A method of depositing a plurality of layers on an article, the method comprising steps of:

flowing a plasma gas in a plasma generation chamber in communication with a deposition chamber, the deposition chamber having a lower pressure than the plasma generation chamber, the article being disposed in the deposition chamber;

generating an arc in the plasma generation chamber to create a plasma, which flows into the deposition chamber;

injecting a first material comprising an organometallic material and a first oxidant into the plasma and reacting the first material to form an interlayer on the article, the interlayer comprising a polymerized organosilicon material; and

injecting a second material comprising an organosilicon material and a second oxidant into the plasma and reacting the second material to form a second layer comprising an inorganic ultraviolet absorbing material on the interlayer, the second material comprising a gaseous reagent, wherein the interlayer has a coefficient of thermal expansion that is between that of the substrate and the second layer.

Please substitute the following for pending Claim 5:

5. (Amended) The method of claim 4, wherein the first material or the second material comprises an evaporated elemental metal.

Please substitute the following for pending Claim 6:

6. (Amended) The method of claim 4, further comprising the step of injecting a third material into the plasma to form a third layer and reacting the third material to form a third layer comprising an abrasion resistant material on the second layer.

Please substitute the following for pending Claim 7:

7. (Amended) The method of claim 6, wherein the first material comprises a first organosilicon material, the second material comprises an evaporated elemental metal, and the third material comprises a third organosilicon material, and the method further comprises the step of injecting a third oxidant with the third material.

Please substitute the following for pending Claim 57:

57. (Amended) The method of claim 4, wherein the substrate comprises glass.

REMARKS

Applicants have submitted herewith a division of Serial No. 09/ Application Serial No. 09/271,654, filed March 17, 1999, and respectfully request that the accompanying Preliminary Amendment be entered. Claims 1-3, 9-11, 13-16, 20-51 and 59-61 have been canceled, without prejudice. As such, Claims 4-7, 12, 17-19, 52-58, and 62-73 remain in the case.

The Examiner is invited to telephone the Applicants' counsel at the number provided below in order to resolve any outstanding issues concerning the present application.

Respectfully submitted,



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ATTACHMENT A

Marked-up versions of amended Claims 4-7 and 57 are provided below.

Marked-up version of Claim 4:

4. (Amended) A method of depositing a plurality of layers on an article, the method comprising steps of:

flowing a plasma gas in a plasma generation chamber in communication with a deposition chamber, the deposition chamber having a lower pressure than the plasma generation chamber, the article being disposed in the deposition chamber;

generating an arc in the plasma generation chamber to create a plasma, which flows into the deposition chamber;

injecting a first material comprising an organometallic material and a first oxidant into the plasma and reacting the first material to form an interlayer on the article, the interlayer comprising a polymerized organosilicon material; and

injecting a second material comprising an organosilicon material and a second oxidant into the plasma and reacting the second material to form a second layer comprising an inorganic ultraviolet absorbing material on the interlayer, the second material comprising a gaseous reagent, wherein the interlayer has a coefficient of thermal expansion that is between that of the substrate and the second layer [The method of claim 1, wherein the first material comprises an organometallic material, the second material comprises an organosilicon material, and the method further comprises the steps of:

injecting an oxidant with the first material; and

injecting an oxidant with the second material].

Marked-up version of Claim 5:

5. (Amended) The method of claim [1]4, wherein the first material or the second material comprises an evaporated elemental metal.

Marked-up version of Claim 6:

6. (Amended) The method of claim [1]4, further comprising the step of injecting a third material into the plasma to form a third layer and reacting the third material to form a third layer comprising an abrasion resistant material on the second layer.

Marked-up version of Claim 7:

7. (Amended) The method of claim 6, wherein the first material comprises [an] a first organosilicon material, the second material comprises an evaporated elemental metal, and the third material comprises [an] a third organosilicon material, and the method further comprises the [steps] step of

[injecting an oxidant with the second material; and]

injecting [an] a third oxidant with the third material.

Marked-up version of Claim 57:

57. (Amended) The method of claim [1]4, wherein the substrate comprises glass.